Supplementary materials

A study on the effect of ambient air plasma treatment on properties of perovskite films

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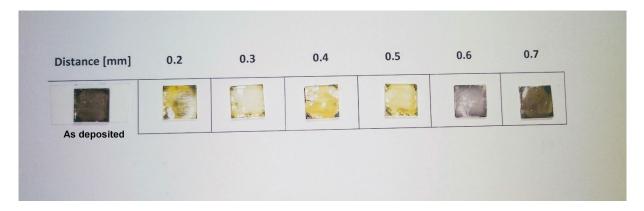


Figure S1. The photo of plasma treated perovskite films with different distances.

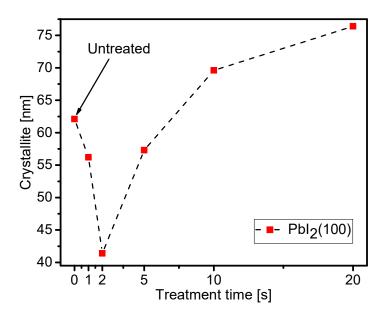
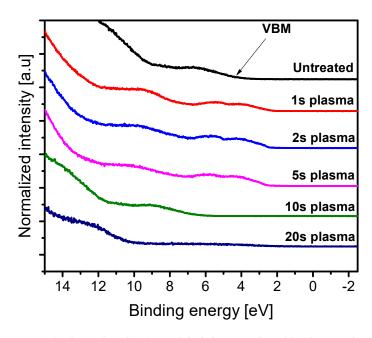


Figure S2. Crystallite size of PbI₂ at plate of (100) before and after plasma treatment.



 $\textbf{\it Figure S3}. \ \textit{Variation of valance bands of mixed-halide perovskite film during plasma treatment.}$

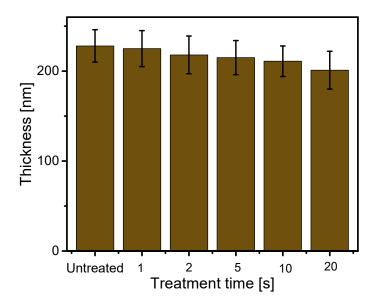


Figure S4. Variation the thickness of mixed-halide perovskite during plasma treatment time.